

AMENDMENTS TO THE CLAIMS

Claims 1 to 9. (Canceled)

Claim 10. (Previously Presented) A positive-working chemical-amplification photoresist composition which consists of, as a uniform solution in an organic solvent:

(A) 100 parts by weight of a film-forming resinous compound having acid-dissociable solubility-reducing groups in the molecule and capable of being imparted with an increased solubility in an aqueous alkaline solution by interaction with an acid, which resinous compound is a copolymeric resin consisting of from 50 to 85% by moles of the monomeric units of hydroxystyrene, from 10 to 30% by moles of the monomeric units of styrene and from 2 to 20% by moles of the monomeric units of a tert-alkylacrylate or methacrylate;

(B) from 1 to 20 parts by weight of an acid-generating compound which is an onium salt compound having a fluoroalkylsulfonate as the anionic constituent;

(C) from 0.01 to 5 parts by weight of a phosphorus-containing oxo acid,

(D) an amine selected from the group consisting of secondary amines and tertiary amines, in an amount sufficient to exhibit a quenching effect and

(E) an organic solvent to dissolve components (A) to (D).

Claim 11. (New) The positive-working chemical-amplification photoresist composition as claimed in claim 10 in which the phosphorus-containing oxo acid as the component (C) is selected from the group consisting of phosphoric acid, phosphorous acid, phosphonic acid, phosphinic acid, phenylphosphinic acid and phenylphosphonic acid.

Claim 12. (New) The positive-working chemical-amplification photoresist composition as claimed in claim 10 in which the tert-alkyl acrylate or methacrylate is tert-butyl acrylate or methacrylate.

Claim 13. (New) The positive-working chemical-amplification photoresist composition as claimed in claim 10 in which the amount of the phosphorus-containing oxo acid as the component (C) is in the range from 0.1 to 2.0 parts by weight per 100 parts by weight of the component (A).

Claim 14. (New) The positive-working chemical-amplification photoresist composition according to claim 10 wherein the amine is triethylamine, tributylamine, dibutylamine or triethanolamine.